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APPLICATION NO.		FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/736,709		12/17/2003	Yong-Sung Ham	0630-1835P	5806	
2292	7590	06/30/2005		EXAM	EXAMINER	
		T KOLASCH & BIR	CHACKO DAV	CHACKO DAVIS, DABORAH		
	O BOX 747 CALLS CHURCH, VA 22040-0747			ART UNIT	PAPER NUMBER	
				1756		
				DATE MAILED: 06/30/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
Office Action Summary	10/736,709	HAM, YONG-SUNG				
Office Action Summary	Examiner	Art Unit				
The MAN INO DATE of the community of	Daborah Chacko-Davis	1756				
The MAILING DATE of this communication apperent of the second for Reply	ears on the cover sheet with the c	orrespondence address				
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	6(a). In no event, however, may a reply be tim within the statutory minimum of thirty (30) days ill apply and will expire SIX (6) MONTHS from cause the application to become ABANDONEI	nely filed s will be considered timely. the mailing date of this communication. D (35 U.S.C. § 133).				
Status						
1)⊠ Responsive to communication(s) filed on 17 De	ecember 2003.					
2a) ☐ This action is FINAL . 2b) ☑ This	action is non-final.					
3) Since this application is in condition for allowan	Since this application is in condition for allowance except for formal matters, prosecution as to the ments is					
closed in accordance with the practice under E	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.					
Disposition of Claims						
 4) ☐ Claim(s) 1-18 is/are pending in the application. 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-18 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or 						
Application Papers						
9)☐ The specification is objected to by the Examiner						
10)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.						
Applicant may not request that any objection to the d		• •				
Replacement drawing sheet(s) including the correction 11) The oath or declaration is objected to by the Example 11.						
Priority under 35 U.S.C. § 119		· · · · · · · · · · · · · · · · · · ·				
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priori application from the International Bureau * See the attached detailed Office action for a list of	have been received. have been received in Application ty documents have been received (PCT Rule 17.2(a)).	on No d in this National Stage				
Attachment(s)	 □					
 Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 12/03. 	4)					
S. Patent and Trademark Office						

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 2. Claims 1-18, are rejected under 35 U.S.C. 102(e) as being anticipated by U. S. Patent Application Publication No. 2003/0124865 (Baek et al).

Baek, in [0010], [0015], [0016], [0017], [0029], [0030], [0031], [0033], [0034], [0035], and in figures 3A through 3D, discloses a method of forming a pattern comprising providing a substrate wherein a plurality of panels and process-subjected layers are formed, wherein the substrate includes plurality of areas (forming display panels on a large area of the substrate), providing a cliché with recesses (plurality of grooves), filling the recesses with resist, and transferring the resist formed in the recesses of the cliché to the process-subjected layer of the substrate by using a printing roll (transfer roll), with the same width (desired size) as that of the panel in the display device (substrate area), that rotates and contacts the surface of the cliché, and transferring the blanket of the resist formed on the transfer roll to the process-subjected layer by rotating and contacting the surface of the process-subjected layer (claims 1-3,

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5, 11-12, 17, and 18). Baek, in [0017], [0033], [0034], [0035], discloses that the length of the resist to be transferred (blanket) is the same as the circumference of the transfer roll which in turn is the same as the length of the panel (divided area of the substrate) (claims 4, 13). Baek, in [0034], and [0035], discloses that the cliché, and the transfer roll have the same size as that of the panel (divided area of the substrate) (claims 6-7). Baek, in [0031], [0035], discloses that the process-subjected layer (etching object layer) may be a metal layer, or a semiconducting layer or an insulating layer such as SiOx or SiNx (claims 8-10, 14-16).

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Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Daborah Chacko-Davis whose telephone number is (571) 272-1380. The examiner can normally be reached on M-F 9:30 - 6:00. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Mark F Huff can be reached on (571) 272-1385. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306. Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you

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have questions on access to the Private PAIR system, contact the Electronic Business

Center (EBC) at 866-217-9197 (toll-free).

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June 27, 2005.

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